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Harrison
Patent

Attorney's Docket No. 015290-440

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Rajinder Dhindsa et al.

Application No.: 09/689,845

Filed: October 13, 2000

For: STEPPED UPPER ELECTRODE
FOR PLASMA PROCESSING
UNIFORMITY

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) Group Art Unit: 2813

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) Examiner: K. Christianson

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TECHNOLOGY CENTER 2800

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AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the Official Action dated September 26, 2001, please amend the application as follows.

IN THE CLAIMS:

Sub B2
Please replace Claim 19 as follows:

19. (Amended) A plasma chamber for use in manufacturing a semiconductor device, said plasma chamber including a top electrode and a bottom electrode having opposed surfaces facing each other and spaced apart from one another to define a gap therebetween, the bottom electrode comprising a substrate support, and the opposed surface of the top electrode being an exposed surface comprising a central portion and a step projecting from a peripheral portion thereof and extending at least partially around the central portion, the step controlling a localized density of the plasma formed adjacent the exposed surface of the top electrode.